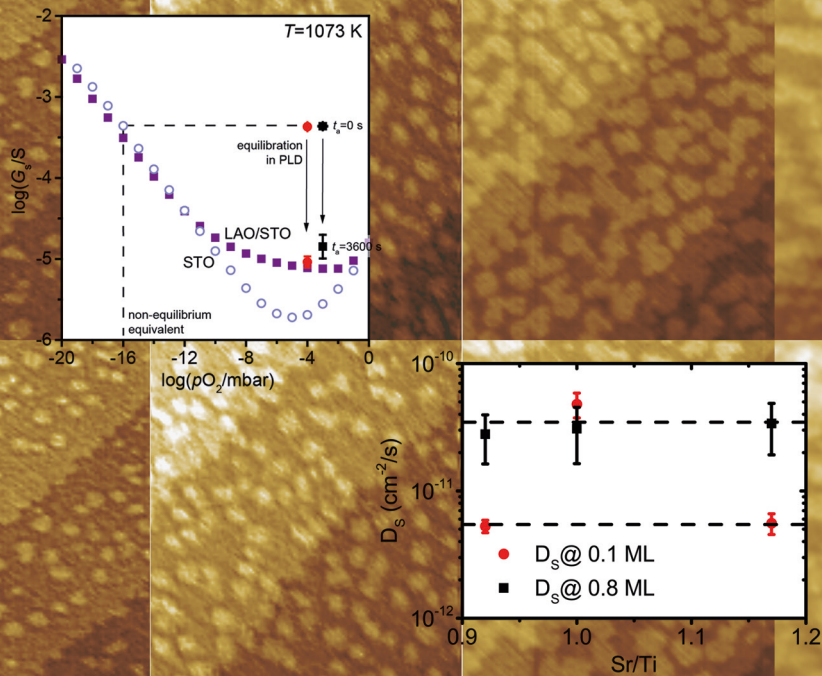


In situ studies of the growth and oxidation of complex metal oxides by pulsed laser deposition

Chencheng Xu



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